Semiconductor physics

Raman study of thin TIInS₂ films prepared by thermal evaporation

Y.M. Azhniuk¹, A.V. Gomonnai¹, V.V. Lopushansky¹, O.O. Gomonnai², T.Y. Babuka², V.Y. Loya¹, L.M. Suslikov², I.M. Voynarovych¹

Abstract. Thin (10...200 nm) TlInS₂ films are prepared by thermal evaporation on silicon and silicate glass substrates. Micro-Raman spectra measured at a rather moderate excitation (532 nm, 4 kW/cm^2) confirm amorphous character of the films. Narrow features emerging in the spectra at a higher excitation power density (40 kW/cm²) testify crystallization of TlInS₂ on the film surface. The formation of crystallites is explained by thermal effect of the absorbed laser light. The film surface is shown to be heated above 150 °C by the 40 kW/cm^2 laser beam.

Keywords: amorphous films, Raman spectroscopy, crystallization, thermal treatment.

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1. Introduction

Crystalline TlInS₂ is a well-known semiconductor material with highly anisotropic layered structure. At low temperatures, it possesses ferroelectric properties and at 190...220 K, it exhibits an incommensurate phase [1-3]. It has been extensively studied [1–9] due to its promising applications in optoelectronics caused by its high photosensitivity in the visible spectral range, high birefringence, and broad transparency range as well as good thermoelectric characteristics and demonstration of photoinduced phenomena enabling memory effects [2, 10]. TlInS₂ is known to crystallize in various structures and polytypes, the most typical and extensively studied being the ones described by 6 C2h [4, 5] and 18 D4h [4] space groups. Important information on the crystal structure and lattice dynamics of TlInS2 can be provided by Raman spectroscopy [4, 5, 8, 9, 11 and references therein].

Recent years demonstrate a growing interest of researchers to $TIInS_2$ thin films [12–15], similarly to the films of other I–III–VI₂ type materials mostly prepared by thermal evaporation [16–22]. Here, we report on a Raman spectroscopy study of thermally evaporated $TIInS_2$ thin films.

2. Experimental

TlInS₂ films were obtained by thermal evaporation of pre-synthesized crystalline TlInS₂ (the synthesis details are described in an earlier study [11]) onto silicate glass and crystalline Si substrates kept at room temperature.

The evaporation temperature was close to 1050 K, the evaporation rate was 4 nm/s, and the pressure was $\sim 2 \cdot 10^{-4} \text{ Pa}$. The thickness d of the thicker films was evaluated by interferometry. The thickness of the thinner films was obtained by interpolation taking into account the evaporation time and was estimated to range from 10 to 200 nm. No post-preparation annealing of the films was performed.

Micro-Raman scattering measurements were performed at room temperature using a XPloRa Plus spectrometer (Horiba) equipped with a cooled CCD camera. Excitation was provided by a solid-state laser ($\lambda_{exc} = 532$ nm). The instrumental resolution was better than 2.5 cm⁻¹.

3. Results and discussion

Raman spectra of the TIInS₂ films on Si and silicate glass substrates measured at low excitation power density $(P_{\rm exc}=4~{\rm kW/cm^2})$ are shown in Fig. 1. Broad maxima in the spectra (compared to those reported for single-crystalline TIInS₂ [9, 11]) are typical for non-crystalline materials, thereby characterizing the films as amorphous. The spectral position of the asymmetric broad maximum at 270...290 cm⁻¹ for different samples correlates with the known Raman features of crystalline TIInS₂ corresponding to internal vibrations of ${\rm In_4S_6}$ units in the TIInS₂ structure [5]. Evidently, one would hardly expect the existence of ${\rm In_4S_6}$ units in amorphous TIInS₂ films. However, it is quite reasonable to assume that these maxima for the films with different thicknesses correspond to In–S bond vibrations, while broad lower-frequency

¹Institute of Electron Physics, NAS of Ukraine, 21 Universytetska Street, 88017 Uzhhorod, Ukraine

²Uzhhorod National University, 3 Narodna Square, 88000 Uzhhorod, Ukraine

^{*}Corresponding author e-mail: yu.azhniuk@gmail.com

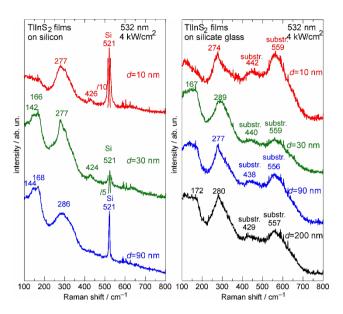


Fig. 1. Micro-Raman spectra of TlInS₂ films of different thicknesses d thermally evaporated on silicon and silicate glass substrates. The spectra were measured at the excitation with $\lambda_{\rm exc} = 532$ nm and $P_{\rm exc} = 4$ kW/cm².

features in the range of 140...175 cm⁻¹ most likely origin from vibrations of Tl-S bonds. A weak maximum near 425 cm⁻¹, which is observed only for the films on Si substrates and is masked by the scattering from the substrate for the films on silicate glass, has not been reported for crystalline TlInS₂ [5, 9, 11]. Most likely, it is related to vibrations of homopolar S-S bonds in the films. The maxima in the spectra of the films of different thicknesses are similar. As expected, the thinner the films, the higher are the intensities of the substrate-related maxima in the observed Raman spectra (Fig. 1).

It should be noted that the spectra of the films shown in Fig. 1 drastically differ from those of thermally evaporated TlInS₂ films reported in a recent study [15], where the spectral features are more distinct and resemble those of crystalline TlInS₂ [5, 11]. Crystallinity of the TlInS₂ films from Ref. [15] (or at least presence of crystalline TlInS₂ phase in the films) is also supported by X-ray diffraction data showing narrow reflexes typical for TlInS₂. The reason why in our case, contrary to the study [15], thermal evaporation resulted in amorphous TlInS₂ films, is evidently related to the evaporation procedure. As follows from our recent study of TlInSe2 films prepared by a similar procedure [23], the substrate temperature can play a crucial role. Namely, evaporation of TlInSe₂ onto substrates preheated to 300 °C resulted in polycrystalline films [19, 20], while evaporation onto non-preheated substrates led to formation of amorphous TlInSe₂ films [23]. In our case, evaporation of TlInS₂ films was performed onto cold substrates without any preheating. Meanwhile, the details of the evaporation procedure are described in a rather contradictory manner in Ref. [15]. Therefore, we were not able to find sufficient information to identify particular factors responsible for fabrication of amorphous or polycrystalline TlInS₂ films.

Other studies of TIInS₂ films reported earlier did not include Raman spectroscopy. However, the reported XRD data clearly confirmed the film polycrystalline nature [13]. The authors of [14] do not discuss the structure of the obtained TIInS₂ films, nor do they give the details of the substrate temperature during evaporation. Meanwhile, in an earlier study [12] claiming the films to be amorphous, the same films not subjected to any additional treatment were simultaneously stated to be crystallized in tetragonal, monoclinic, and rhombic structures. This, without any Raman or XRD data provided, makes the study [12] self-contradictory. Therefore, to the best of our knowledge, the present paper is the first one reporting on fabrication and study of amorphous TIInS₂ films.

Comparison of the measured Raman spectra of the TlInS₂ films (Fig. 1) with those of bulk TlInS₂ crystals (Fig. 2) shows that the positions of the intense broad maxima in the spectra of the amorphous films correlate to those of the much narrower peaks of crystalline TlInS₂. In particular, the broad band with the maximum position in the spectra of the films varying from 274 to 286 cm⁻¹ (Fig. 1) corresponds to the two most intense features of crystalline TlInS₂ at 280 and 292 cm⁻¹ assigned to "intramolecular" vibrations of In₄S₁₀ tetrahedral groups in the TlInS₂ structure (Fig. 2). Evidently, the same broad band in the spectrum of the amorphous film also includes a contribution from vibrations corresponding to a less intense feature at 345 cm⁻¹ in the spectrum of the TlInS₂ crystal. Meanwhile, the lower-frequency broad feature with the maximum at around 170 cm⁻¹ (and sometimes an additional shoulder or maximum near 140 cm⁻¹) in the spectra of the films is evidently related to vibrations of Tl-S bonds in the amorphous film structure. In the spectrum of the TlInS₂ crystal it is represented by a peak at 140 cm⁻¹ (Fig. 2), although a weak maximum at 172 cm⁻¹ was also reported [9]. The weak high-frequency feature near 425 cm⁻¹ in the spectra of the films prepared on Si substrate (it is masked by a broad substrate-related feature for the films on silicate glass) should most probably be ascribed to S-S vibrations, since the vibrations with participation of heavier Tl and In atoms

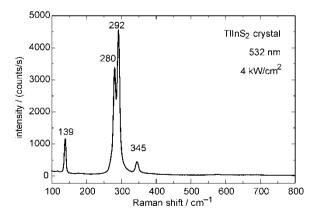


Fig. 2. Micro-Raman spectrum of TlInS₂ crystal measured in $Z(XX + XY)\overline{Z}$ scattering configuration at the excitation with $\lambda_{\rm exc} = 532$ nm and $P_{\rm exc} = 4$ kW/cm².

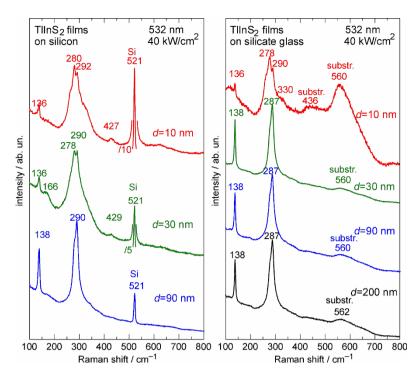


Fig. 3. Micro-Raman spectra of TlInS₂ films of different thicknesses d thermally evaporated on silicon and silicate glass substrates. The spectra were measured at the excitation with $\lambda_{\rm exc} = 532$ nm and $P_{\rm exc} = 40$ kW/cm².

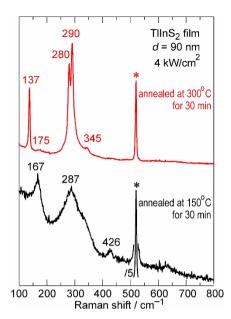


Fig. 4. Micro-Raman spectra of TlInS₂ films with the thickness d = 90 nm on Si substrates annealed for 30 min at 150 °C and 300 °C. The spectra were measured at the excitation with $\lambda_{\rm exc} = 532$ nm and $P_{\rm exc} = 4$ kW/cm². Asterisks mark the 521 cm⁻¹ peak from the Si substrate

are expected to have much lower frequencies. However, vibrations of S–S bonds are more likely to be expected at somewhat higher frequencies, around 460...490 cm⁻¹, in particular, for amorphous chalcogenides [24, 25].

In the Raman spectra of the same TlInS2 films measured at a higher $P_{\text{exc}} = 40 \text{ kW/cm}^2$, relatively sharp peaks at 136...138 cm⁻¹ as well as in the range of 278...290 cm⁻¹ are revealed (Fig. 3). These peaks may be related to rapid localized crystallization of the films under irradiation by a laser beam. For the thinner films (evaporated on Si substrates with d = 10 nm and 30 nm and on silicate glass substrate with d = 10 nm), one can clearly see two peaks in the range of 278...290 cm⁻¹, where the most intense Raman features of crystalline TlInS₂ are revealed (see Fig. 2). Evidently, the orientation of crystallites formed in the irradiated area is random. One may expect therefore that Raman modes of all the allowed symmetries will be revealed in the spectra. The sharp features at 136...138 cm⁻¹ and 278...290 cm⁻¹ emerging after the irradiation are the most intense for TlInS₂ in this spectral range [4, 5, 7, 11] and are readily observed therefore.

It can be also seen that the crystalline-like features in the spectra of the films measured at $P_{\rm exc}=40~{\rm kW/cm^2}$ are considerably narrower for the thicker films, while for the thinner films they partially retain the "amorphous-like" features of the low- $P_{\rm exc}$ spectra, namely the broad high-frequency wing of the feature centered at $278...290~{\rm cm^{-1}}$ and the weak feature near $425~{\rm cm^{-1}}$ (Fig. 3). Besides, it is seen that the features typical for amorphous materials are retained for the thinner films on

Si substrates much better than for the films on silicate glass substrates. Evidently, the reasons for this are related to the mechanism of film transformation under illumination by a tightly focused laser beam.

The photoinduced crystallization of TlInS₂ in the amorphous film can result from the material heating due to absorption of light in the laser spot. Recently, we applied Raman spectroscopy to observe a similar effect for TlInSe₂ films. In these films TlInSe₂, TlSe, and In₂Se₃ crystallites were formed under intense illumination [23]. On the other hand, photoinduced formation of TlInSe₂ crystallites in an amorphous As₂Se₃-based material under intense laser illumination was reported earlier for Tl-In-As-Se glass [26] as well as formation of II-VI chalcogenide nanocrystals in amorphous As₂S₃-based [25] or As₂Se₃-based [27] films was demonstrated. In these cases, the photoinduced crystallization was based on a nonthermal mechanism of photofluidization of the amorphous material (a drastic drop of its viscosity) upon illumination, which also led to an accompanying effect of photoinduced mass transport with formation of a pit in the laser spot on the amorphous film surface [25–27].

Meanwhile, in our case, the film surface remained undamaged after Raman measurements and, contrary to the earlier studies [25–27], no signs of mass transport were observed in the optical microscope used for the Raman measurements. The mechanism of localized crystallization in the illuminated films during Raman measurements at an increased $P_{\rm exc}$ must be purely thermal. The illuminating light is absorbed by the sample surface that causes an increase of temperature of the amorphous

film in the laser spot thereby locally enhancing the atom mobility and resulting in a reconfiguration of the film structure with formation of more energetically favourable crystallites.

We performed an experiment to check directly the effect of thermal treatment on the amorphous TlInS₂ film structure. The Raman spectra of the 90-nm thick TlInS₂ films annealed during 30 min. at 150 °C and 300 °C are shown in Fig. 4. In order to avoid additional heating of the samples during the Raman measurements, low value $P_{\rm exc} = 4 \text{ kW/cm}^2$ was chosen. As can be seen from Fig. 4, annealing of a film at 150 °C does not result in any visible changes of the Raman spectrum compared to the one for the as-prepared sample (Fig. 1), clearly confirming its amorphous structure. However, thermal treatment at a higher temperature (300 °C) leads to drastic changes in the spectrum with appearance of distinct peaks of crystalline TlInS₂ at 137, 280, 290, and 345 cm⁻¹, very much similar to those of single-crystalline TlInS₂ (Fig. 2) and to the spectra of the films measured at high $P_{\rm exc}$ (Fig. 3). This clearly confirms that the effect of $TIInS_2$ crystallization induced by high- P_{exc} illumination is driven by the thermal mechanism. One may conclude that illumination of TlInS₂ films with $P_{\text{exc}} = 40 \text{ kW/cm}^2$ results in the sample heating above 150 °C.

As mentioned above, photoinduced crystallization of the thinner (10...30 nm) films is retarded compared to that of the thicker (90...200 nm) films. Moreover, this retardation is more pronounced for the films evaporated onto Si substrates compared to the films on silicate glass substrates. We believe that this is due to the fact that heat dissipation occurs faster for the thinner films due to the higher thermal conductivity of the substrate compared to that of the film material [28]. Hence, the laser light energy absorbed by a thinner film is dissipated faster and the temperature required for crystallization cannot be achieved so fast. Moreover, as crystalline silicon has much higher thermal conductivity than silicate glass [28], the thinner films on Si substrates dissipate heat even faster.

Comparing the obtained data with the results of a similar study of TlInSe₂ films with similar characteristics prepared by the same technique [23], one should mention that for TlInSe₂ the temperature of 150 °C is sufficient to initiate film crystallization. Besides, while heating (both photoinduced and applied directly) of the TlInSe₂ films leads to formation of several crystalline phases (TlInSe₂, TlSe, and In₂Se₃) [23], a single phase (TlInS₂) is formed in our case.

4. Conclusions

TllnS₂ films with the thicknesses from 10 to 200 nm were obtained by thermal evaporation on silicon and silicate glass substrates kept at room temperature. As follows from the micro-Raman spectra measured at $\lambda_{\rm exc} = 532$ nm and a laser power density $P_{\rm exc} = 4$ kW/cm², the structure of the films is amorphous, contrary to the data of other authors [15] for the films evaporated onto heated substrates. To our knowledge, this is the first study of amorphous TllnS₂ films reported so far.

Raman spectra measured at a higher $P_{\text{exc}} = 40 \text{ kW/cm}^2$ exhibit narrow features, which evidence formation of TlInS₂ crystallites on the film surface. The film crystallization in the laser spot is shown to originate from the thermal effect of a tightly focused laser light absorbed by the film, which facilitates diffusion of atoms in the illuminated area and rearrangement of the film structure. Low- $P_{\rm exc}$ Raman measurements performed for the 90-nm TlInS₂ film annealed for 30 min at 300 °C confirm this conclusion, showing remarkably similar crystallite-related peaks. Meanwhile, the Raman spectrum of a similar film annealed for 30 min at 150 °C completely retains the features characteristics for amorphous films. Hence, laser light illumination by $P_{\text{exc}} = 40 \text{ kW/cm}^2$ heats the film surface to the temperature above 150 °C. Crystallization is slower for thinner films due to the higher heat dissipation because of the higher thermal conductivity of the substrates with respect to the film material.

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Authors and CV



Yuriy M. Azhniuk, Dr.Sci., Senior Researcher at the Department of Materials for Functional Electronics, Institute of Electron Physics, NASU. Authored over 100 research papers. The area of his scientific interests includes semiconductor physics, physics of nanosystems, Raman spectroscopy, and materials science.

http://orcid.org/0000-0002-9414-0252



Alexander V. Gomonnai, Dr.Sci., Head of the Department of Materials for Functional Electronics, Institute of Electron Physics, NASU. Authored over 110 research papers and 8 patents. The area of his scientific interests includes semiconductor physics, physics of nanosystems, Raman spectroscopy, and materials science.

E-mail: gomonnai@ukr.net, http://orcid.org/0000-0002-8826-1453



Vasyl V. Lopushansky, PhD, Senior Researcher at the Department of Materials for Functional Electronics, Institute of Electron Physics, NASU. Authored over 60 research papers. The area of his scientific interests includes semiconductor physics, Raman spectroscopy, and

materials science. E-mail: lvv702@gmail.com, http://orcid.org/0000-0002-9414-0252



Oleksandr O. Gomonnai, PhD, Associate Professor at the Department of Optics, Uzhhorod National University. Authored over 35 scientific papers and 1 patent. The area of his scientific interests includes inorganic chemistry, solid state chemistry, crystal growth, and materials

science. E-mail: oleksandr.gomonnai@uzhnu.edu.ua, https://orcid.org/0000-0003-3240-2947



Tetyana Y. Babuka, PhD, Senior Researcher at the Institute of Physics and Chemistry of Solid State, Uzhhorod National University. Authored over 25 articles. The area of her scientific interests includes solid state physics, quantum chemistry, and computational physics.

E-mail: tetyana.babuka@uzhnu.edu.ua, https://orcid.org/0000-0001-5583-1459



Vasyl Y. Loya, PhD, Senior Researcher at the Department of Materials for Functional Electronics, Institute of Electron Physics, NASU. Authored over 30 research papers. The area of his scientific interests includes semiconductor physics, thin films, and materials science.

E-mail: vasyl.loya@gmail.com, http://orcid.org/0000-0002-7945-0367



Leonid M. Suslikov, Dr.Sci., Professor at the Department of Applied Physics, Uzhhorod National University. Authored over 200 scientific papers and 28 patents. The area of his scientific interests includes semiconductor physics, optics, and applied physics.

E-mail: leonid.suslikov@uzhnu.edu.ua, http://orcid.org/0000-0003-4628-5972



Ivan M. Voynarovych, PhD, Senior Researcher at the Department of Materials for Functional Electronics, Institute of Electron Physics, NASU. Authored nearly 20 research papers. The area of his scientific interests includes semiconductor physics, thin films, and materials science.

E-mail: voynar@ukr.net, http://orcid.org/0000-0003-1888-2139

Authors' contributions

Azhniuk Y.M.: investigation, writing – original draft, writing – review and editing.

Gomonnai A.V.: conceptualization, writing – review and editing.

Lopushansky V.V.: methodology, investigation.

Gomonnai O.O.: conceptualization, methodology, investigation.

Babuka T.Y.: investigation. Loya V.Y.: investigation.

Suslikov L.M.: supervision, resources. Voynarovych I.M.: investigation.

Раманівське дослідження тонких плівок TIInS2, отриманих методом термічного напилення

Ю.М. Ажнюк, А.В. Гомоннай, В.В. Лопушанський, О.О. Гомоннай, Т.Я. Бабука, В.Ю. Лоя, Л.М. Сусліков, І.М. Войнарович

Анотація. Тонкі (10...200 нм) плівки $TIInS_2$ отримано методом термічного напилення на підкладках з кремнію та силікатного скла. Мікрораманівські спектри, виміряні при помірній інтенсивності збуджуючого світла $(532 \text{ нм}, 4 \text{ кВт/см}^2)$, підтверджують аморфний характер плівок. Вузькі особливості, які з'являються у спектрах при вищій густині потужності збудження (40 кВт/см^2) , свідчать про кристалізацію $TIInS_2$ на поверхні плівки. Утворення кристалітів пояснюється термічним ефектом поглиненого лазерного світла. Показано, що поверхня плівки нагрівається лазерним променем потужністю 40 кВт/см^2 до температури понад 150 °C.

Ключові слова: аморфні плівки, раманівська спектроскопія, кристалізація, термічна обробка.